


Day : Tuesday

Date: 4/8/2003

PALM INTRANETTime:  
11:37:09**Inventor Name Search Result**

Your Search was:

Last Name = INAGAKI

First Name = NORIHIRO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>10058925</u>	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	INAGAKI, NORIHIRO
<u>09793879</u>	Not Issued	030	02/28/2001	METHOD AND SYSTEM FOR PYROLYZING PLASTIC AND PYROLYSATE PRODUCT	INAGAKI, NORIHIRO
<u>09680268</u>	<u>6472080</u>	150	10/06/2000	THIN COPPER FILM DIRECTLY BONDED POLYIMIDE FILM AND METHOD OF MANUFACTURING THE SAME	INAGAKI, NORIHIRO
<u>09586790</u>	Not Issued	161	06/05/2000	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	INAGAKI, NORIHIRO
<u>07563321</u>	<u>5086286</u>	150	07/26/1990	GAS-SENSITIVE DEVICE	INAGAKI, NORIHIRO

**Inventor Search Completed: No Records to Display.**Search Another:  
Inventor

Last Name

INAGAKI

First Name

NORIHIRO

Search

Day : Tuesday

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**Inventor Name Search Result**

Your Search was:

Last Name = TASAKA

First Name = SHIGERU

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>10058925</u>	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	TASAKA, SHIGERU
<u>09793879</u>	Not Issued	030	02/28/2001	METHOD AND SYSTEM FOR PYROLYZING PLASTIC AND PYROLYSATE PRODUCT	TASAKA, SHIGERU
<u>09680268</u>	<u>6472080</u>	150	10/06/2000	THIN COPPER FILM DIRECTLY BONDED POLYIMIDE FILM AND METHOD OF MANUFACTURING THE SAME	TASAKA, SHIGERU
<u>09586790</u>	Not Issued	161	06/05/2000	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	TASAKA, SHIGERU
<u>06657196</u>	<u>4607386</u>	150	10/03/1984	HANDWRITTEN CHARACTER RECOGNITION DEVICE	TASAKA , SHIGERU
<u>06651778</u>	<u>4591465</u>	150	09/18/1984	METHOD OF PRODUCING POLYMERIC ELECTRET ELEMENT	TASAKA , SHIGERU

Inventor Search Completed: No Records to Display.

Day : Tuesday  
Date: 4/8/2003Time:  
11:38:02

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## Inventor Name Search Result

Your Search was:

Last Name = NAKAJIMA

First Name = TETSUYA

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>10058925</u>	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	NAKAJIMA, TETSUYA
<u>09709423</u>	Not Issued	120	11/13/2000	DIELECTRIC ELEMENT AND METHOD FOR FABRICATING THE SAME	NAKAJIMA, TETSUYA
<u>09586790</u>	Not Issued	161	06/05/2000	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	NAKAJIMA, TETSUYA
<u>09463793</u>	<u>6353078</u>	150	01/27/2000	POLYURETHANE ADHESIVE, METHOD FOR USE IN BONDING, AND USE OF MIXTURE	NAKAJIMA, TETSUYA
<u>09413895</u>	Not Issued	161	10/07/1999	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAJIMA, TETSUYA
<u>09269881</u>	<u>6120969</u>	150	04/02/1999	POLYPHENOL COMPOUND, QUINONEDIAZIDE ESTER	NAKAJIMA, TETSUYA

				AND POSITIVE PHOTORESIST COMPOSITION	
<u>09194394</u>	<u>6087466</u>	150	11/25/1998	POLYURETHANES AND POLYESTER POLYOLS	NAKAJIMA, TETSUYA
<u>08575030</u>	<u>5672895</u>	150	12/19/1995	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAJIMA, TETSUYA
<u>08194988</u>	<u>5500542</u>	150	02/14/1994	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAJIMA, TETSUYA
<u>07472585</u>	<u>4971469</u>	150	01/30/1990	AUTOMATIC PAPER LOADING MECHANISM AND METHOD FOR PRINTER	NAKAJIMA, TETSUYA
<u>07323757</u>	<u>4975544</u>	150	03/15/1989	CONNECTING STRUCTURE FOR CONNECTING CONDUCTORS IN AN ELECTRONIC APPARATUS	NAKAJIMA, TETSUYA
<u>06625674</u>	<u>4747083</u>	150	06/28/1984	SEMICONDUCTOR MEMORY WITH SEGMENTED WORD LINES	NAKAJIMA, TETSUYA

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4/8/03 11:38 AM

L Number	Hits	Search Text	DB	Time stamp
1	45	silane near2 coupl\$6 same (alkoxy methoxy ethoxy) with (hydroxy\$1 OH) and (ethanol methanol alcohol) same heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:48
2	69	silane near2 coupl\$6 same (alkoxy methoxy ethoxy) with (chlor\$6 halogen) and (ethanol methanol alcohol) same heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:19
3	0	(trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane) near3 coupl\$6 and (ethanol methanol alcohol) same heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:21
4	1	(trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane) near3 coupl\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:23
5	465	(trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) same (coupling coupler)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:25
6	154	(trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) near5 (coupling coupler)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:27
7	8	((trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) same (coupling coupler) ) same (silica (silicon near3 (oxide dioxide))) same (plastic polymer polypropylene binder)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:29
8	2	((trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) near5 (coupling coupler) ) same (ethanol methanol alcohol) same heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:49
9	2	((trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) near5 (coupling coupler) ) same (ethanol methanol alcohol) same (heat\$4 celsius)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:51
10	2	((trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) same (coupling coupler) ) same (ethanol methanol alcohol) same (heat\$4 celsius)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:51
11	19	((trialkoxylalkyl\$1silane dialkoxylalkyl\$1silane methyltrimethoxysilane methyltriethoxysilane isobutyltrimethoxysilane dimethyldimethoxysilane dimethyldiethoxysilane) near5 (coupling coupler) ) and (ethanol methanol alcohol) with (heat\$4 celsius)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:52
-	0	(polymer\$4 polyolefin polypropylene polyethylene plastic) near9 surface near9 ((discharge near2 glow) plasma) near9 oxygen near9 functionality	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:01

-	452	(polymer\$4 polyolefin polypropylene polyethylene plastic) near9 surface near9 ((discharge near2 glow) plasma) near9 (oxygen air)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:28
-	501	(polymer\$4 polyolefin polypropylene polyethylene plastic) near9 surface near9 ((discharge near2 glow) plasma) near9 (oxygen air hydroxy\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:22
-	39	((polymer\$4 polyolefin polypropylene polyethylene plastic) near9 surface near9 ((discharge near2 glow) plasma) near9 (oxygen air)) near9 hydroxy\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:19
-	18	((polymer\$4 polyolefin polypropylene polyethylene plastic) near9 surface near9 ((discharge near2 glow) plasma) near9 (oxygen air)) near9 subsequent\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:23
-	75	( polyolefin polypropylene polyethylene) with (hydroxy\$2 functional\$7) with ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:39
-	33	( polyolefin polypropylene polyethylene) near9 (hydroxy\$2 functional\$7) near9 ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:36
-	1	(polypropylene PP) near9 surface near9 (modif\$9 functional\$8) near9 hydroxy\$2 near9 ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:45
-	42	(( polyolefin polypropylene polyethylene) with (hydroxy\$2 functional\$7) with ((discharge near2 glow) plasma)) not (( polyolefin polypropylene polyethylene) near9 (hydroxy\$2 functional\$7) near9 ((discharge near2 glow) plasma))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:40
-	383	(polypropylene PP) and surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma) same (hydroxy\$2 oxygen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:47
-	127	(polypropylene PP) and surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma) same hydroxy\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:48
-	21	(polypropylene PP) same surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma) same hydroxy\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:54
-	143	polypropylene same surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:00

-	56	polypropylene with surface near9 (modif\$9 functional\$8) with ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:56
-	0	(polypropylene with surface near9 (modif\$9 functional\$8) with ((discharge near2 glow) plasma)) with (air atmosphere oxygen) near5 (exposure subsequent\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:17
-	1	(polypropylene with surface near9 (modif\$9 functional\$8) with ((discharge near2 glow) plasma)) with (air atmosphere)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:58
-	18	(polypropylene same surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma)) same (air atmosphere)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:58
-	45	(polypropylene same surface near9 (modif\$9 functional\$8) same ((discharge near2 glow) plasma)) same (air atmosphere oxygen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 17:59
-	96	polypropylene same surface near9 (oxygen hydroxy\$2) near9 ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:01
-	106	polypropylene same surface near9 (oxygen hydroxy\$2) with ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:01
-	21	polypropylene same surface near9 hydroxy\$2 with ((discharge near2 glow) plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:16
-	3	surface near9 hydroxy\$2 with ((discharge near2 glow) plasma) with (air atmosphere oxygen) near5 (exposure subsequent\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:20
-	11	hydroxy\$2 with ((discharge near2 glow) plasma) with (air atmosphere oxygen) near5 (exposure subsequent\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 18:22
-	10	((discharge near2 glow) plasma) with (air atmosphere oxygen) near9 (exposure subsequent\$5) near9 hydroxy\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 19:38
-	67	silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r near3 deposition)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 20:01

-	17	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r near3 deposition) ) with silicon near2 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 19:47
-	0	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r near3 deposition) ) with "SiO.sub.x"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 19:48
-	3	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r near3 deposition) ) and "SiO.sub.x"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 19:48
-	0	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r near3 deposition) ) with polymerization near2 plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 20:01
-	3	silane near9 oxygen same plasma near9 ((chemical near3 vapo\$1r near3 deposition) CVD) same polymerization	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 20:16
-	3	4557946.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/15 20:16
-	54	plasma near9 surface near9 silane near2 coupl\$7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 11:20
-	0	(plasma near9 surface near9 silane near2 coupl\$7) with hydroxy\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 11:19
-	10	plasma near9 surface with silane near2 coupl\$7 with (covalent\$4 chemical\$4 react\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 14:43
-	5	hydroxy\$4 near9 surface with silane near2 coupl\$7 with heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 11:43
-	3	hydroxy\$4 near9 surface with silane near2 coupl\$7 with (heat\$4 temperature) with react\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 11:56
-	5	hydroxy\$4 near9 surface with silane near2 coupl\$7 with heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 12:00



-	29	hydroxy\$4 with silane near2 coupl\$7 with heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 12:24
-	49	"5229172"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 14:35
-	2	"6129956"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 14:35
-	0	alcohol near3 solution with silane near2 coupl\$5 with (heating (elevated near2 temperature)) with hydroxy\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 14:46
-	0	alcohol near3 solution with silane near2 coupl\$5 with ((heating heated) (elevated near2 temperature)) with hydroxy\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 15:02
-	0	alcohol with silane near2 coupl\$5 with ((heating heated) (elevated near2 temperature)) with hydroxy\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 15:16
-	9	(alcohol with silane near2 coupl\$5 with hydroxy\$4) with surface	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 15:13
-	51	alcohol with silane near2 coupl\$5 with hydroxy\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 15:17
-	32	alcohol with silane near2 coupl\$5 with (chemical\$4 covalent\$4 react\$6) with surface	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 16:14
-	117	alcohol with (aqueous water) with solution with ((coupling near2 agent) coupler silane) with (chemical\$4 covalent\$4 react\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 16:38
-	73	kbm-602	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 16:14
-	1	dialkyldialkoxy\$1silane near6 (coupl\$7 (adhesion near2 promot\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:39

-	1	(dialkyldialkoxy\$1silane dipropyldimethoxy\$1silane) near6 (coupl\$7 (adhesion near2 promot\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 16:42
-	10	(dialkyldialkoxy\$1silane dipropyldimethoxy\$1silane) with heat\$9	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 16:43
-	0	dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:41
-	0	dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:41
-	124	silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:51
-	0	alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:48
-	26	silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/16 17:53
-	26	(plasma discharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:16
-	0	((plasma discharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:16
-	51	(plasma discharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:16
-	0	((plasma discharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon near3 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:11
-	496	silane near3 coupl\$4 same (silicon near3 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:45

77	(silane near3 coupl\$4 same (silicon near3 oxide)) and barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:13
1	(plasma discharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4 same silicon near3 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:20
2	(plasma discharge) same (polyolefin polypropylene polyester plastic) and ((silane near3 coupl\$4 same (silicon near3 oxide)) and barrier)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:18
46	(plasma discharge) and ((silane near3 coupl\$4 same (silicon near3 oxide)) and barrier)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:20
0	(plasma discharge) near9 pre\$1 treat\$9 and ((silane near3 coupl\$4 same (silicon near3 oxide)) and barrier)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:21
127	(plasma discharge) near9 (pre\$1 treat\$9 treat\$9) and (silane near3 coupl\$4 same (silicon near3 oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:45
21	"5131590"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 17:39
5	"5763028"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:44
97	silane near3 coupl\$4 same (silicon near3 oxide) near3 (layer film)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 15:32
16	(plasma discharge) near9 (pre\$1 treat\$9 treat\$9) and (silane near3 coupl\$4 same (silicon near3 oxide) near3 (layer film))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:26
24384	plasma near3 discharge	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:44
3	(silane near3 coupl\$4 same (silicon near3 oxide) near3 (layer film)) and (plasma near3 discharge)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:44

-	807	reactive near4 deposition near9 plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:47
-	27	(reactive near4 deposition near9 plasma) same silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:46
-	16	(reactive near4 deposition near9 plasma) with silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:48
-	457	reactive near2 deposition near9 plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:56
-	10	(reactive near2 deposition near9 plasma) with silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:51
-	15	(reactive near2 deposition near9 plasma) same silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:53
-	5	((reactive near2 deposition near9 plasma) same silane) not ((reactive near2 deposition near9 plasma) with silane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:52
-	443	plasma same silane with oxygen same silicon near2 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:57
-	44	(plasma same silane with oxygen same silicon near2 oxide) same sputtering	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:56
-	0	(plasma same silane with oxygen same silicon near2 oxide) same reactive near2 sputtering	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:56
-	4	reactive near2 deposition same (plasma same silane with oxygen same silicon near2 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:56
-	24	(plasma same silane with oxygen same silicon near2 oxide) same barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 20:57

-	96	silane near3 coupl\$4 with (Sio\$2 (silicon near3 oxide)) near3 (layer film)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 15:35
-	4	"5695836"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:14
-	2999	((silicon near3 (dioxide oxide mon\$2oxide)) SiOx) same sputtering same plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 19:01
-	100	((silicon near3 (dioxide oxide mon\$2oxide)) SiOx) same sputtering same plasma) same silane same oxygen	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 18:54
-	40	((silicon near3 (dioxide oxide mon\$2oxide)) SiOx) same sputtering same plasma) same silane same oxygen) and barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 18:54
-	635	silicon near9 dioxide near9 (oxide mon\$2oxide SiOx) with plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 19:03
-	1	silicon near9 dioxide near9 (oxide mon\$2oxide SiOx) with plasma with silane with oxygen same barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 19:04
-	3	silicon near9 dioxide near9 (oxide mon\$2oxide SiOx) with plasma with silane with oxygen and barrier near9 (oxygen gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:44
-	20	silicon near9 (dioxide oxide mon\$2oxide SiOx) with plasma with silane with oxygen and barrier near9 (oxygen gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 19:06
-	39	chlor\$1silane with alkoxy\$1silane with coupl\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:18
-	4	chlor\$1silane with alkoxy\$1silane with coupl\$6 with (hydroxy\$1 oh) near2 group	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:16
-	39	(chlor\$1silane dichlor\$1silane) with alkoxy\$1silane with coupl\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:20

-	2	(chlor\$1silane with alkoxy\$1silane with coupl\$6) with alcohol	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:19
-	25	alkoxy\$1silane with coupl\$6 with alcohol	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:31
-	59	alkoxy with silane near2 coupl\$6 with alcohol	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:32
-	7	alkoxy with silane near2 coupl\$6 same solution near9 alcohol	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:36
-	8	alkoxy with silane near2 coupl\$6 same solution near9 (ethanol methanol alcohol)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:38
-	2	silane near2 coupl\$6 same solution near9 (ethanol methanol alcohol) same heat\$6 same percent	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:41
-	103	silane near2 coupl\$6 same solution near9 (ethanol methanol alcohol) same heat\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 21:10
-	62	silane near2 coupl\$6 near9 solution near9 (ethanol methanol alcohol) same heat\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:54
-	0	silicon near3 (dioxide oxide) same ( silane near2 coupl\$6 near9 solution near9 (ethanol methanol alcohol) same heat\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:45
-	6	( silane near2 coupl\$6 near9 solution near9 (ethanol methanol alcohol) same heat\$6) same (alkoxy methoxy ethoxy)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:45
-	0	( silane near2 coupl\$6 same solution near9 (ethanol methanol alcohol) same heat\$6) same plasma near9 treat\$9	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:55
-	1	( silane near2 coupl\$6 same solution near9 (ethanol methanol alcohol) same heat\$6) same plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/07 20:55

-	19	silane near2 coupl\$6 same (ethanol methanol alcohol) same heat\$6 same (hydroxy\$1 oh)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/08 09:14
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